

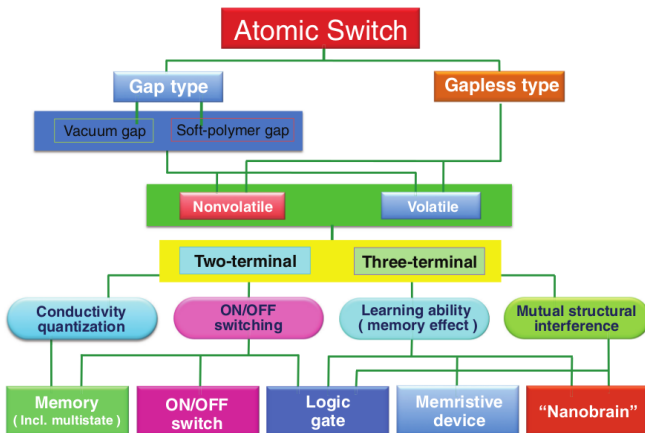
Memresistive switching in Ag_2S solid electrolyte

Gubicza Ági

Nanophysics seminar

2012. december 6.

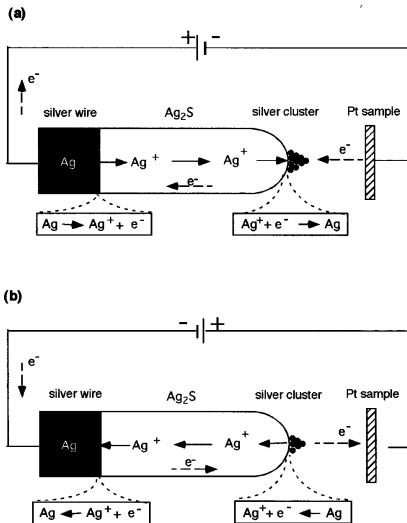




¹T. Hasegawa et al., *Atomic Switch: Atom/Ion Movement Controlled Devices for Beyond Von-Neumann Computers*, *Adv.Mat.* **24**, 252 (2012)

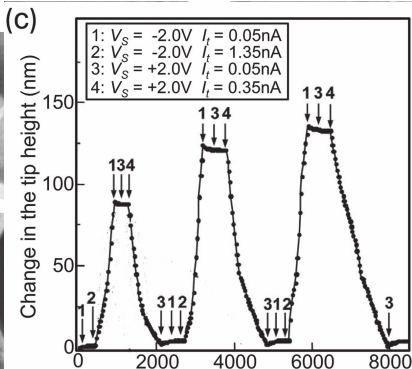
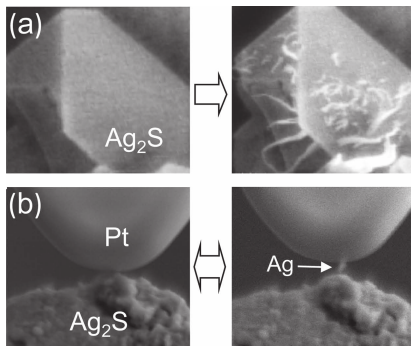
Gap-type atomic switch

- e^- injection into an Ag_2S crystal: reduction of cations, precipitation on the surface
- SEM: controlling the position and irradiation time of the e^- beam: Ag nanodots can be formed in a patterned structure
- STM mode ² or crossbar structure



²K. Terabe et al., JAP, **91**, 12 (2002)

Gap-type atomic switch - STM mode



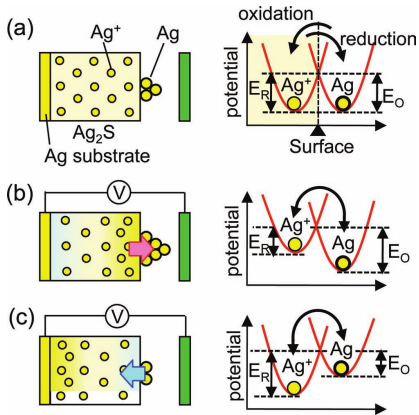
$$\frac{dl}{dt} = A \exp(-D \cdot I_t)$$

$\frac{dl}{dt}$ does not depend on bias

A, D : coefficients

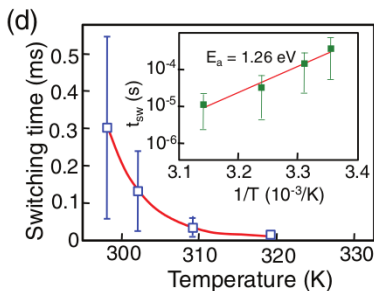
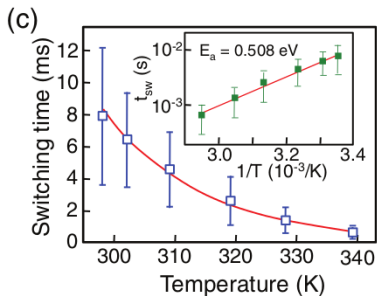
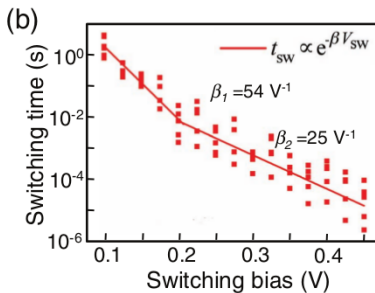
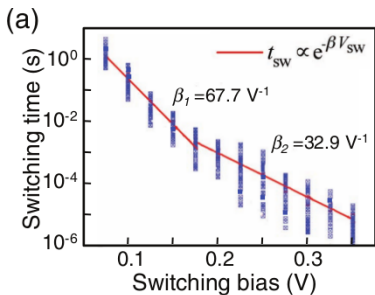
I_t: tunnel current

Gap-type atomic switch - crossbar structure

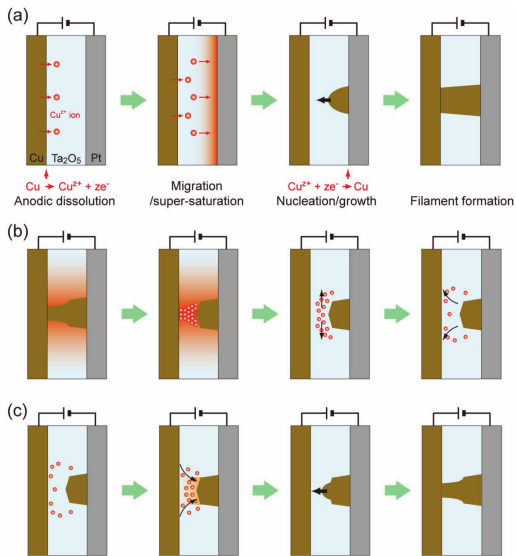


- 10^5 switches
- switching time: R decreases from $1 \text{ M}\Omega$ to $12.9 \text{ k}\Omega$

Crossbar structure - switching time



Gapless-type atomic switch



- conductive path is made in an ionic conducting material
- forming process
- electric field-driven activated hopping
- min. switching time: 5 ns
- Ag_2S : on/off ratio: 10^5 , switching speed: 1 ms

Shortest switching time

Cu bridge in an insulator ³

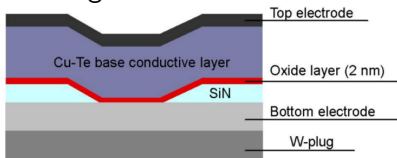
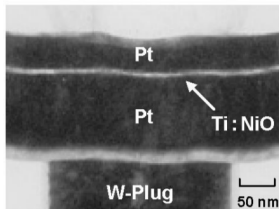


Table 1. Typical parameters and key features.

FEOL	180-nm CMOS
Active cell area	40 nm ϕ
Set pulse width	5 ns
Set current	110 μ A
Set voltage	+3 V
Reset pulse width	1 ns
Reset current	125 μ A
Reset voltage	-1.7 V
Resistance read voltage	+0.1 V
Endurance	10 ⁷ cycles

redox reactions: Ti-doped NiO ⁴

- 5 ns switching time
- series transistor: current limiter during the set
- symmetric, unipolar
- long reset time, large reset current



³K. Aratani et al., IEEE Int. Electron Dev. Meeting, 2007, pp 783-786

⁴K. Tsunoda et al., IEEE Int. Electron Dev. Meeting, 2007, pp 767-770

Towards a quantitative description of solid electrolyte conductance switches⁵

Theory: Hebb and Wagner model

$$-eV = \varepsilon''_F - \varepsilon'_F = \mu''_e - \mu'_e \quad (1)$$

' : Ag electrode, '' : Pt electrode

$$\mathbf{j}_e = \frac{\sigma_e}{e} \nabla \mu_e \quad (2) \quad \mathbf{j}_{Ag^+} = -\frac{\sigma_{Ag^+}}{e} \nabla \mu_{Ag^+} \quad (3)$$

local thermodynamic equilibrium:

$$\mu_{Ag} = \mu_{Ag^+} + \mu_e \quad (4)$$

$$-eV = (\mu''_{Ag} - \mu'_{Ag}) - (\mu''_{Ag^+} - \mu'_{Ag^+}) \quad (5)$$

$t \gg 0$:

$$\nabla \mu_{Ag^+} = 0, j_{Ag^+} = 0 \quad (6)$$

$$\nabla \mu_e = \nabla \mu_{Ag}, j_{total} = j_e \quad (7)$$

⁵Morales-Masis, Ruitenbeek et al., *Nanoscale*, **2**, 2275 (2010)

Towards a quantitative description of solid electrolyte conductance switches

$$e\mathbf{j}_{total}(\mathbf{r}) \cdot d\mathbf{r} = \sigma_e d\mu_{Ag} \quad (8)$$

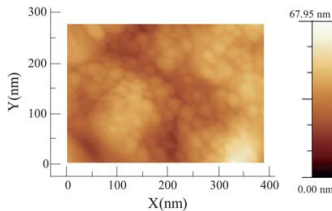
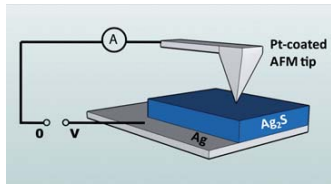
$$e \int_{r''}^{r'} \mathbf{j}_{total}(\mathbf{r}) \cdot d\mathbf{r} = -\frac{e}{K} I \quad (9)$$

$$\sigma_e = \sigma_0 e^{(eV/kT)}$$

$$I(V) = K\sigma_0 \frac{k_B T}{e} \left(e^{(eV/K_B T)} - 1 \right) \quad (10)$$

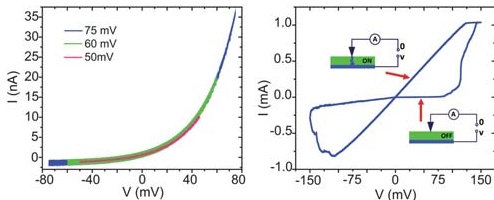
in AFM geometry: $K = 2\pi a$

Towards a quantitative description of solid electrolyte conductance switches



- deposition of Ag_2S : sputtering Ag in Ar/ H_2S plasma on top of a Ag film
- Ag_2S layer thickness: approx. 200 nm, with 30 nm roughness, $5 \times 5 \text{ mm}^2$
- Ag : 100 nm, $10 \times 10 \text{ mm}^2$
- room temperature measurements

Towards a quantitative description of solid electrolyte conductance switches

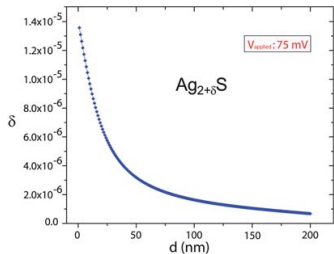
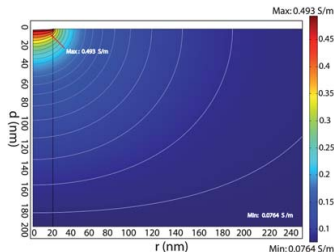


tip contact radius: $a = K/(2\pi) = 12\text{nm}$

Simulation:

$$\delta = n - p = 2K_i^{1/2} \sinh\left(\frac{e(V_0 - V(d))}{kT}\right)$$

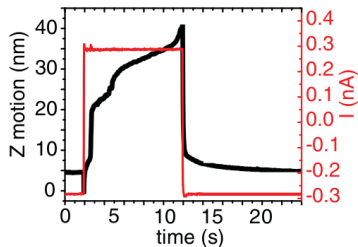
- supersaturation
- nucleation within the silver sulfide



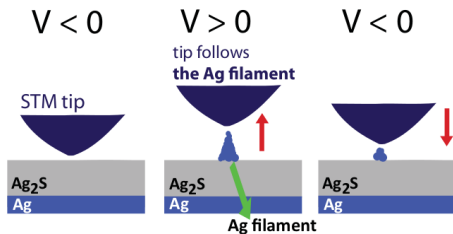
Bulk and surface nucleation processes in Ag₂S conductance switches⁶

the tip is not in contact with the Ag₂S film \Rightarrow gap-type measurement

(a)



(b)

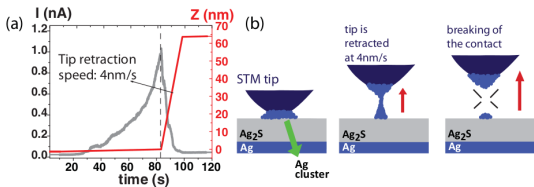
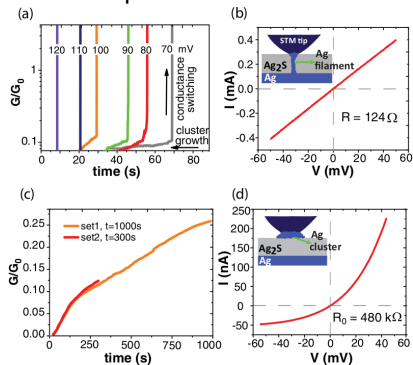


⁵Morales-Masis et al., Phys. Rev. B **84**, 115310 (2011).

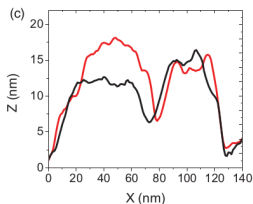
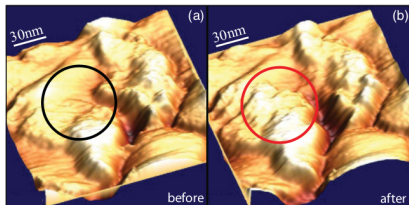
Bulk and surface nucleation processes in Ag₂S conductance switches

the feedback was too slow \Rightarrow gapless-type measurement
sample biased and current measured

two processes: nucleation and cluster formation



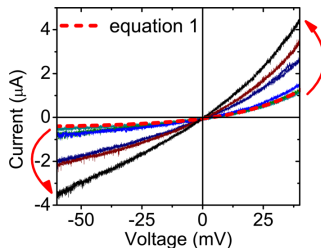
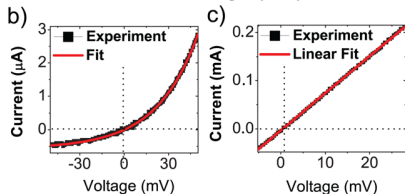
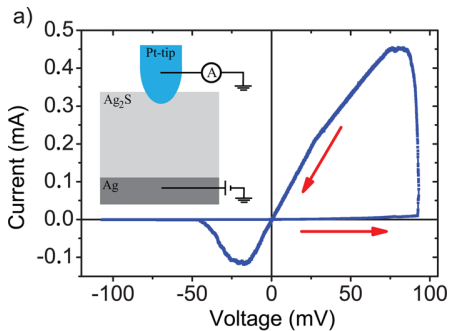
Bulk and surface nucleation processes in Ag_2S conductance switches



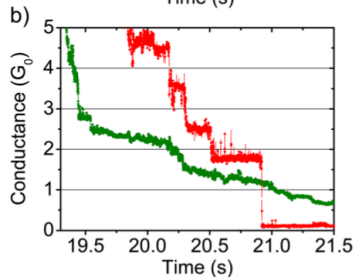
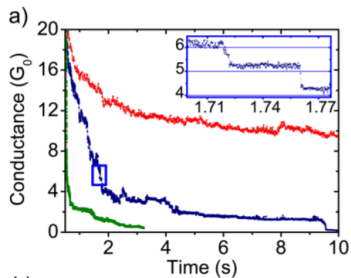
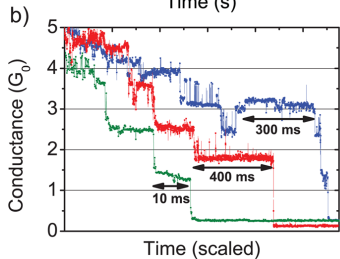
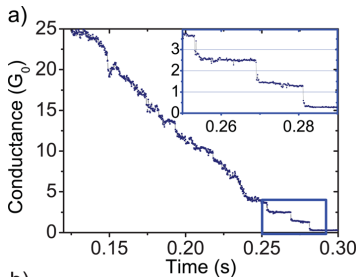
$T=240\text{K}$

100 s between the forming and the topography scan \Rightarrow cluster shrinks back to the Ag_2S

Quantized conductance steps in Ag_2S^7

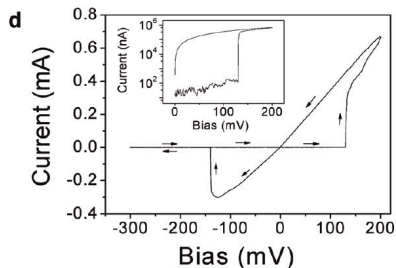
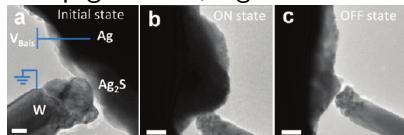


Quantized conductance steps in Ag_2S



Real-Time In Situ HRTEM-Resolved Resistance Switching of Ag₂S Nanoscale Ionic Conductor⁸

W tip grounded, Ag electrode biased



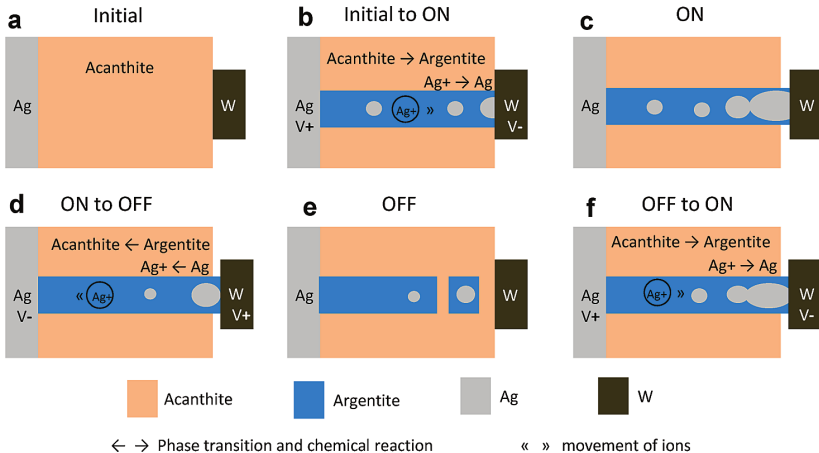
scale bar: a) 20 nm, b)-c) 50 nm

Sample preparation:

- d=0.5 mm Ag wire and S powder annealed in vacuum
- anneal: 200°C, 30 min
- sulfidized Ag wire annealed in argon (200°C, 30 min)
- Ag₂S scratched with a clean Ag wire, small pieces were transferred
- sharp W tip on a piezotube

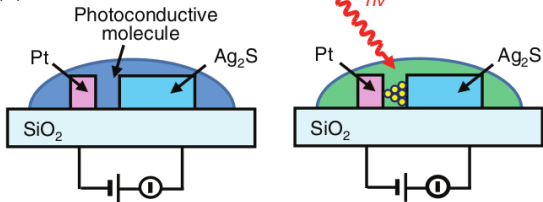
⁷Xu et al., ACS Nano, 4, 5 (2010)

Real-Time In Situ HRTEM-Resolved Resistance Switching of Ag₂S Nanoscale Ionic Conductor

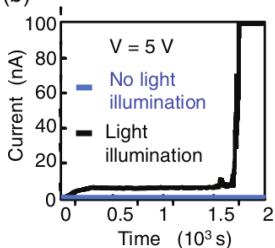


Applications - Photo sensing

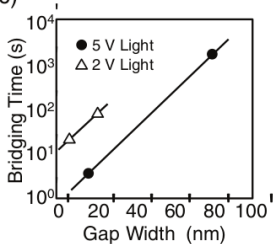
(a)



(b)

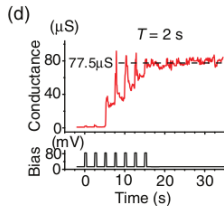
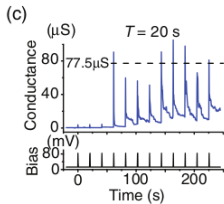
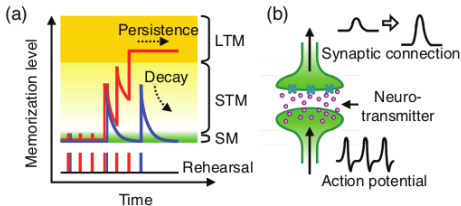
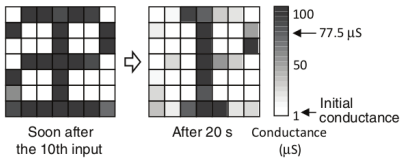


(c)



Applications - Synaptic operations

- short-term plasticity (STP)
- long-term potentiation (LTP)



- 1 T. Hasegawa et al., *Atomic Switch: Atom/Ion Movement Controlled Devices for Beyond Von-Neumann Computers*, *Adv.Mat.* **24**, 252 (2012)
- 2 K. Terabe et al., *JAP*, **91**, 12 (2002)
- 3 K. Aratani et al., *IEEE Int. Electron Dev. Meeting*, pp 783-786 (2007)
- 4 K. Tsunoda et al., *IEEE Int. Electron Dev. Meeting*, pp 767-770 (2007)
- 5 Morales-Masis, Ruitenbeek et al., *Nanoscale*, **2**, 2275 (2010)
- 6 Wanegaar, Ruitenbeek et al., *JAP*, **111**, 014302 (2012)
- 7 Morales-Masis et al., *Phys. Rev. B* **84**, 115310 (2011)
- 8 Xu et al., *ACS Nano*, **4**, 5 (2010)